



Vertical LPCVD/Furnace System

VF/VLF series

Vertical LPCVD/Furnace



VF-001

- Annealing
- 6inch wafer, 5 wafers/batch (include dummy)
- 1-zone heater, max.1000℃
- Alumina reactor
- Alumina pedestal & boat up/down (motor)
- PC control

Annealing in ATM



VF-003

- Firing
- 6inch & 156mm*156mm wafer, 5 wafers/batch (include dummy)
- 1-zone heater, max.1000℃
- Quartz reactor
- Quartz pedestal & boat up/down (motor)
- Flow meter : O2(10slm), N2(10slm)
- PLC & Touch control

Firing in ATM



VLF-003

- Oxidation & P-type diffusion(BBr3)
- 6inch wafer, 4 wafers/batch (include dummy)
- 1-zone heater, max.1150℃
- Quartz reactor
- Quartz pedestal & boat up/down (motor)
- Heater up/down (motor)
- Rotary pump (fomblin oil type)
- Throttle valve + APC controller
- MFC : N2(10slm), N2(500sccm), O2(500sccm), Cl2(100sccm)
- PC control

Oxidation/Diffusion in Vacuum

Vertical LPCVD/Furnace



VLF-004

- Doped poly Si LPCVD
- 6inch wafer, 50 wafers/batch (include dummy)
- 3-zone heater, max.1200 °C
- Quartz reactor + inner tube
- Quartz pedestal & boat up/down (motor)
- Robot arm for wafer auto loading to boat
- Dry pump
- Throttle valve + APC controller
- MFC : SiH4(500sccm), PH3(50sccm), N2(1slm)
- PC control

Doped poly Si LPCVD



VLF-006

- Annealing
- 4inch wafer, 50 wafers/batch (include dummy)
- 3-zone heater, max.1250 °C
- Quartz reactor + inner tube
- Quartz pedestal & boat up/down (motor)
- Dry pump
- Throttle valve + APC controller
- MFC : N2(5slm), O2(5slm)
- PC control

Annealing in Vacuum



VLF-008

- Tube#1 - Wet oxidation
Tube#2 – Silicon nitride LPCVD
- 12inch wafer, 50 wafers/batch (include dummy)
- 3-zone heater, max.1200 °C
- Quartz reactor + inner tube
- Quartz pedestal & boat up/down (motor)
- Dry pump
- Throttle valve + APC controller
- Heating mantle for H2O (3000cc)
- MFC: Tube#1 - O2(10slm),N2(10slm),O2(1slm)
Tube#2 - DCS(1slm), NH3(1slm), N2(5slm), N2(500sccm)
- PC control

2-tube, Oxidation & Silicon Nitride